

University of Massachusetts Lowell purchased Nanonex Advanced Nanoimprint Tool NX 2600

Princeton NJ, Nov. 05. 2009:

Nanonex Corporation, the inventor and world's leading provider in nanoimprint lithography solutions with the longest history, announces the purchase of a Nanonex NX-2600 by University of Massachusetts Lowell. Nanonex is proud to support the leading edge research at the University of Massachusetts Lowell.

The NX-2600 tool was purchased by Prof. Hongwei Sun and his colleagues at University of Massachusetts at Lowell (UML). The NX-2600 will be used as a tool for nanomanufacturing and nano/micro fabrication at UML in the cutting edge research of nanostructure-based chemical and biological sensors, nanoelectronics, nanophotonics, solar cells, MEMS and template-based nanomanufacturing.

On November 5th 2009, Nanonex was invited by University of Massachusetts Lowell to introduce its low-cost, high-throughput, large-area patterning of 3D nanostructures with sub-10 nm resolution and accurate overlay alignment nanoimprint lithography (NIL) solution. The seminar introduced various forms of nanoimprinting, such as thermoplastic, ultraviolet-curable, thermal-curable, and direct imprinting (embossing). The NX imprint tool can be used to meet the needs of a broad spectrum of markets, such as optical devices, displays, data storage, biotech, semiconductor integrated circuits, chemical synthesis, and advanced

materials. Nanonex also introduced its current research in laser assisted direct imprint (LADI). This technology is capable of direct “print” nanopatterns, planarizing rough surface and fill nanotrenches of hard materials through laser melting and imprinting. This project is partially supported by NIST-APT program.

About Nanonex Corporation

Nanonex is the inventor of “nanoimprint lithography”, the world’s first nanoimprint lithography company, and the world’s leading provider of nanoimprint solutions that include equipment, masks, resists and processes. Nanonex’s patented and proprietary nanoimprint lithography (NIL) solutions and Air-Cushion Press™ can manufacture 3D nanostructures with sub-5 nm resolution, large-area uniformity, accurate overlay alignment, high throughput, and low cost. Nanonex NIL solutions have been adopted by a broad spectrum of industry applications, such as optical devices, data storage, displays, light emitting diodes, semiconductor ICs, biotech, chemical synthesis, and advanced materials. Nanonex has over 100 customers and an installed base of more than 40 tools world-wide. Visit www.nanonex.com for additional information.